

Notice of References Cited	Application/Control No. 10/716,006	Applicant(s)/Patent Under Reexamination MEHREGANY ET AL.	
	Examiner Archene Turner	Art Unit 1775	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,103,590 A	08-2000	Swanson et al.	438/409
*	B	US-5,541,023 A	07-1996	Kondo et al.	378/34
*	C	US-5,188,706 A	02-1993	Hori et al.	216/12
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Hurtos et al "Residual stress and texture in poly SiC films grown by low pressure organometallic chemical vapor deposition" Journal of Applied Physic Vol 87, No 415 February 2000, pp 1748-1758
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.